# Advanced INNOSLAB Solid-state-lasers for the generation of bright XUV/EUV-radiation

#### Fraunhofer Institute for Laser Technology (ILT)

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# Outline

Motivation

Requirements

Configuration

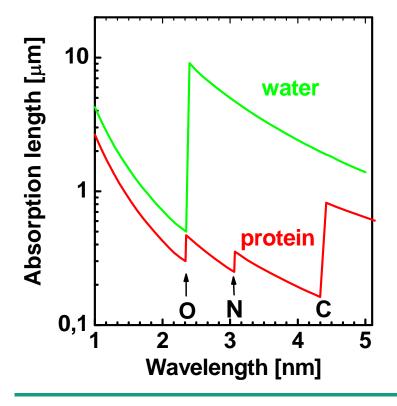
Results

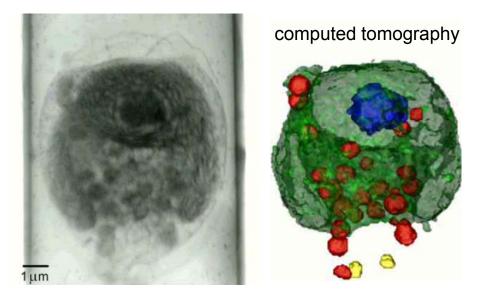
- XUV Generation
- Power, Beam Quality, Pulse Duration
- Diode Seeder
- Regenerative Amplifier
- INNOSLAB pre- and power Amplifier
- Polarization Combining
- Power, Energy, Beam Quality, etc.



# **Motivation**

- Water window (2.4 4.4 nm) is of interest for x-ray microscopy
- Absorption of the surrounding water is smaller than that of organic samples.





Pictures: BESSY, Schneider et al.

from: D. Weiss et al., Ultramicroscopy 84, (2000) 3d structure of frozen Algae

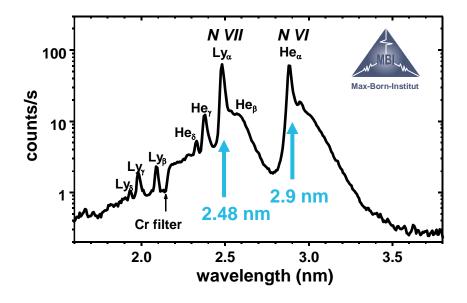


# **Motivation**

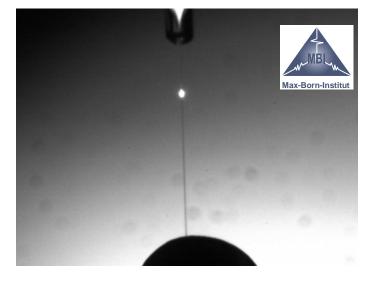
Benefit of **LPP** source in comparison to **DPP** source:

- highly efficiency generation of 2.48 nm and 2.9 nm
- high brightness of the XUV source (only 20 µm source diameter)

Emission spectrum of highly ionized nitrogen.

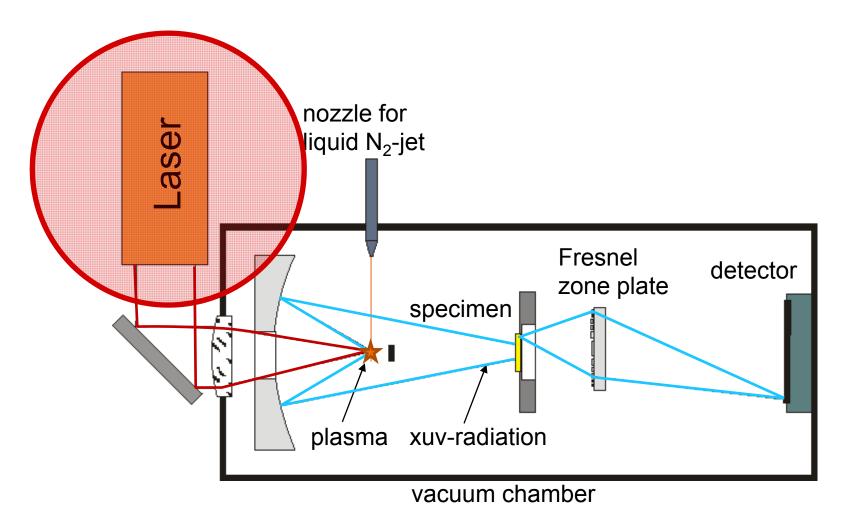


Nitrogen cryo jet laser plasma source.





# Schematic view of a x-ray microscope





# **Evaluation of required laser parameters**

Required XUV-wavelength ("water window"):

XUV-Photon energy:

Electron temperature for photon production :

Required laser intensity  $I_p @ 500 eV$  photon energy:

Power to achieve  $I_p$  (100  $\mu$ m focal diameter):

( 20  $\mu$ m focal diameter):

High brightness of the XUV-spot required

Lower limit of focal diameter given by wavelength, f/D-number and beam quality (M<sup>2</sup>)

Value for Nd:YAG-laser, f/D = 15 and max. beam quality

Upper pulse length limit (no plasma expansion in extend to 20 μm):

low exposure time -> high laser repetition rate, limited by average power:

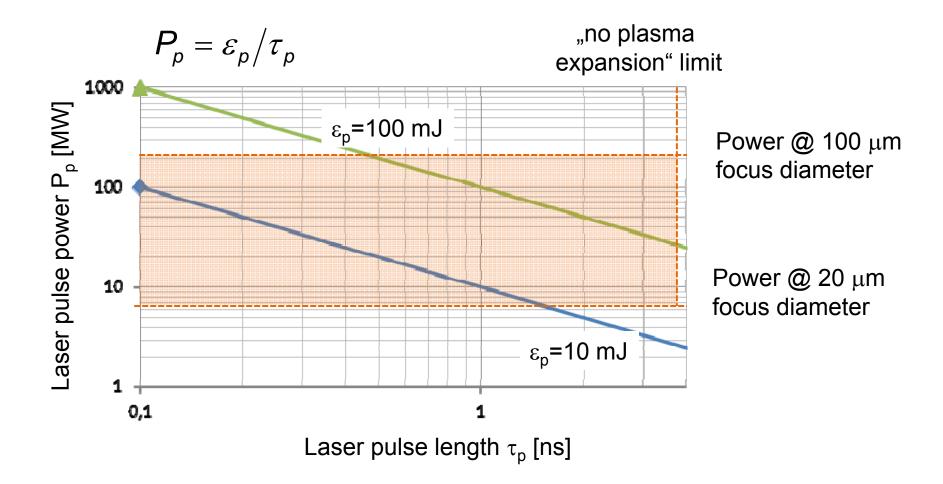
λ ≈ 2.5 nm ε<sub>ph</sub> ≈ 500 eV  $T_e \propto (I_1)^{4/9}$ 2 ·10<sup>12</sup> W/cm<sup>2</sup> 150 MW 6 MW r<sub>f</sub> < 100 µm  $2r_f = M^2 \cdot \frac{4}{\pi} \cdot \frac{t}{D} \cdot \lambda$  $r_{\rm f} > 20 \,\mu m$ 

 $\tau_{\rm p}$  < 5 ns

> kHz



### Laser parameter range: pulse length, energy and power

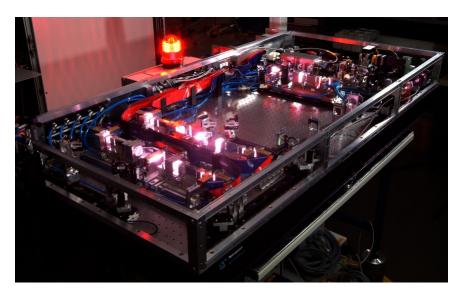




# Laser design goals

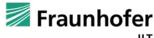
Based on available base technology (solid-state Innoslab laser) a laser with the following parameters is specified:

wave length	1064 nm
pulse length	0,5 – 2 ns
pulse energy, $E_{MP}$	100 - 150 mJ
av. power	200 -300 W
rep. rate	2 kHz
laser power contrast ratio	> 500:1
M <sup>2</sup>	< 2



Contrast ratio =  $E_{MP} / \sum E_{PP}$  (pp-pre pulses)

Laser with a combination of the required parameters (pulse energy and length, average power and repetition rate) are commercially not available.



# **Commercial systems**

Commercially available solid-state lasers (for instance "Innoslab"- lasers of EDGEWAVE or "BrigthLigth" - lasers of JMAR) have:

- Operation: q-switch, MOPA, mode locking
- Continuously/pulsed pumped amplifier stages

Performance of such systems is partly near the desired values, but actually not yet sufficient with respect to pulse length, average power etc.:



Edge-Wave, HD-series

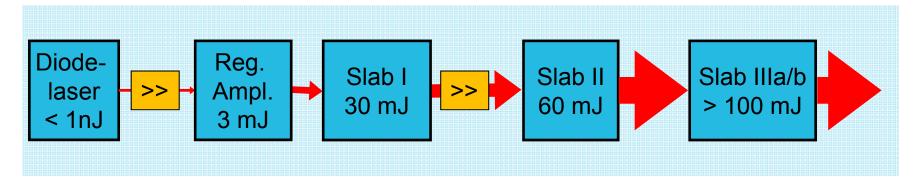


Jmar, "BrigthLigth" series

Development and build-up of an oscillator-amplifier concept with parameters dedicated to the specific EUV-application is necessary



# **Principle set-up**



#### **Diode-laser seeder:**

Rugged and stable concept, variable pulse length, pulse energy < 1 nJ

#### **Regenerative Amplifier:**

- Standard rod shaped active medium,
- Faraday isolator for protection of seed laser

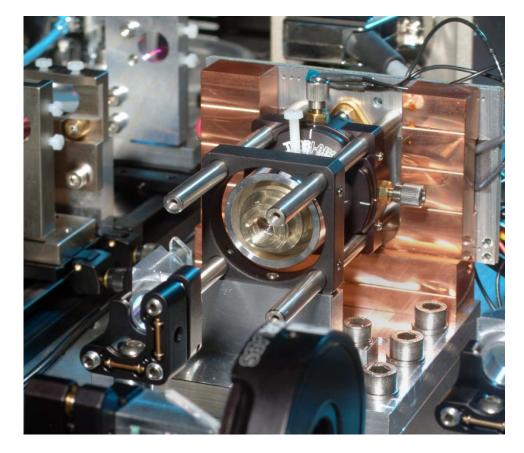
#### Slab shaped amplifiers:

- Large amplification lengths due to adapted folding technique
- High amplification at low beam quality distortion
- Simple adaption of beam size to saturation properties of medium
- optional polarization coupling of two separate lines in final amplifier



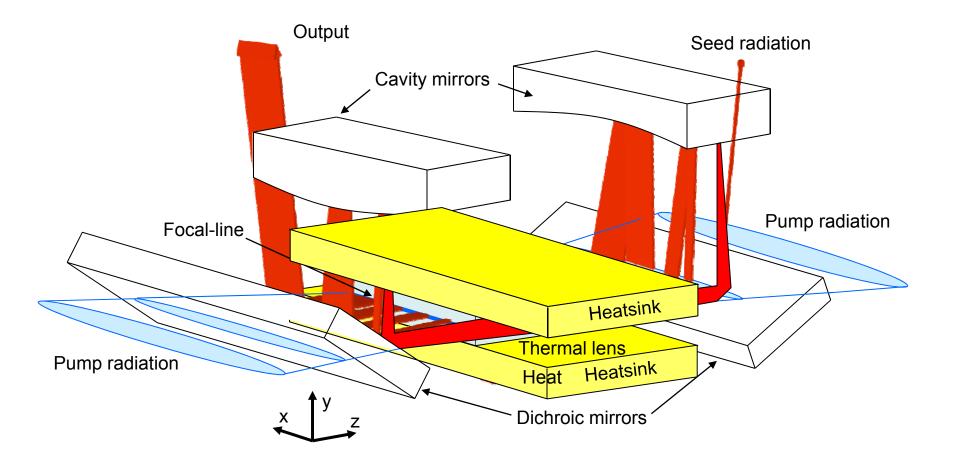
# Diode Seeder for flexible Pulse Generation of 0,5 – 1.5 ns

- Rugged and stable concept
- Control of emission wavelength by grating and temperature
- Pulse shape variable
- External Trigger available
- Computer controlled pulse parameters
- Pulse energy < 1 nJ requires regenerative Amplification



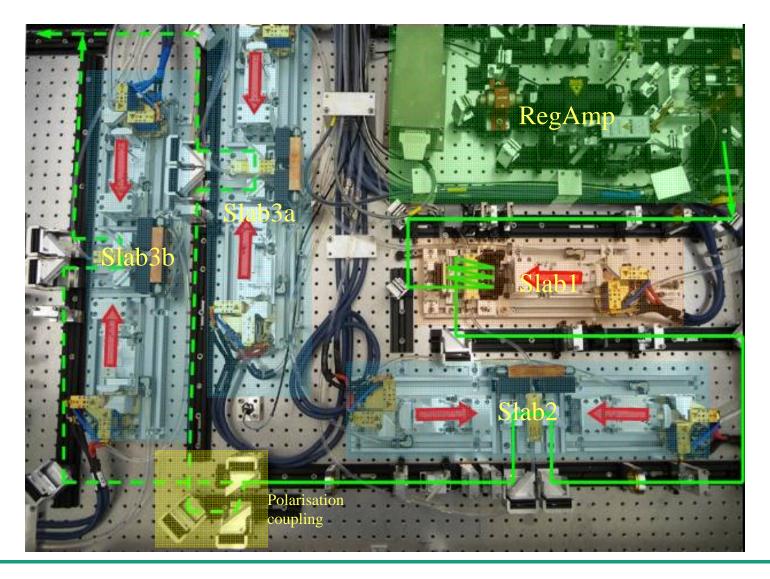


# Slab-laser amplifier – basic design



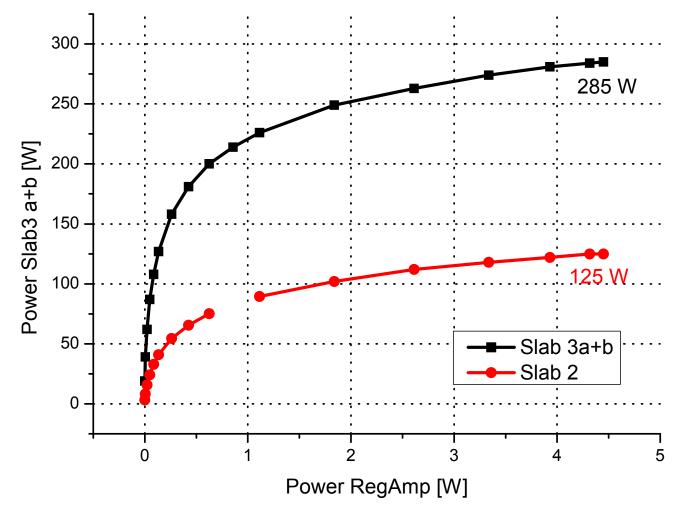


## Laser prototype setup, 150 mJ version





# IR Laser Output of Polarization Combined Power Amplifiers





# 150 mJ – Laser: final results

#### **Design Goals**

pulse duration	0,5 – 2 ns	
wave length	1064 nm	
pulse energy	150 mJ	
power	300 W	
rep. rate	2 kHz	
contrast ratio	> 500:1	
M <sup>2</sup>	< 2	

#### Demonstrated parameters

pulse duration	~ 0,4 ns	V
wave length	1064 nm	V
pulse energy	140 mJ	(
power	280 W	(
rep. rate	2 kHz	V
contrast ratio	> 500:1	V
M <sup>2</sup>	1.4 / 3.4	(



# XUV-results

- one laser @ KTH/Stockholm under preparation for the use in the x-ray microscope (actually: laser characterization and qualification)
- one laser @ MBI/Berlin under initial operation for XUV-production, with the actual data (work in progress):
  - XUV-power more than 5.10<sup>14</sup> ph/s/sr @ 90W laser power (1,3kHz repetition rate)
  - plasma source size not yet measured, estimated to 20 50µm diameter
  - stable operation, optical isolators mandatory
  - thanks to: Herbert Legall, Gernot Blobel und Holger Stiel/MBI Berlin



# **Summary / Outlook**

- Average power of up to 280W @ 2kHz prf out of two coupled beam lines demonstrated
- Peak power of more than 200MW is achieved without beam distortion by nonlinear effects or optical damage
- Contrast ratio better than 500:1
- Beam quality in the range of M<sup>2</sup> < 1.4 ... 3.4 allows efficient plasma generation</p>
- Pulse length can be set from 0.4 ns to 1.5 ns
- Reduction of pulse energy from 140 mJ to about 50 100 mJ considerably simplifies the setup
- Further power scaling by increasing PRF should be possible !



# Acknowlegments

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